

IN THE ABSTRACT:

Please cancel the current abstract and insert the following therefor.

-- An exposure apparatus for exposing a substrate to a pattern of a reticle. The apparatus includes a stage to hold one of the substrate and the reticle, a motor to drive the stage, the motor including a coil and a jacket to cover the coil, and a first adjustment system to adjust temperature of the motor. The first adjustment system includes a flow path of pure water through the jacket, and an impurity removing unit, arranged upstream with respect to the jacket in the flow path, to remove an impurity in the pure water. --